

ABSTRACT

In order to correct specific aberration that occurs within an optical system, a plurality of aberration correction optical elements (4) with differing amounts and/or signs of aberration correction are prepared. The amount and sign of the aberration that is generated within the optical system, except the aberration correction optical elements (4), between a semiconductor laser (1) and an objective lens 6, is then measured using an interferometer or the like. Based on the measured amount and sign of the aberration, where necessary, the aberration correction optical element (4) which, following correction, is most capable of minimizing the residual RMS wave-front aberration is selected from amongst the plurality of different aberration correction optical elements (4), and is then inserted into the optical system between the semiconductor laser (1) and the objective lens (6).